PI 500 S



SUB APERTURE STITCHING INTERFEROMETER SYSTEM FOR PLANO OPTICS

_ precise vertical interferometer for testing flat optical components in full aperture up to diameter/diagonal 600mm

_ integrated, granite based, air-bearing provides precise and maintenance free horizontal and rotational motion

_ easy to operate Tip-/Tilt setting for fringes adjustment

_ automatic stitching pattern calculation according to workpiece shape and size

_ electronic positioning for sub aperture measurementsusing electronic controlled C and Y axis

_ precision, vibration dampened measuring table made of natural granite with high flatness for accurate analyzis

_ adjustable interferometer height for setting best position for different workpiece thicknesses

_ XONOX X-fiz 150 (6“) high performance phaseshifting Fizeau interferometer with 5MPx Cmos camera, stabilized diode laser and electronic control of zoom, focus and contrast

_ innovative, powerful and user friendly fringe analysis system X-fringe PS2 with different smart and intelligent modes to suit various applications in non stitching operation

_ sub aperture stitching software package for X-fringe PS2 allowing full aperture analysis of large flat optical surfaces by combining a calculated number of sub aperture measurements to a full surface analysis.

WORKING RANGE	up to workpiece diameter / diagonal of 480mm
VERSIONS	_ **PI 500 XL** with **X-fiz 150 6“** interferometer, **X-fringe PS2** fringe analyzing system including sub aperture stitching mode
AXIS	_ electronic controlled C-axis with 360° of travel _ electronic controlled Y-axis with 300mm travel _ manually adjustabel tip/tilt
DIMENSIONS (WxDxH)	850 x 1100 x 2150 mm plus additional space for XONOX PC-table (optionally available)
WEIGHT	approx. 800kg
CONNECTIONS	110-240 V / 50-60 Hz, compressed air: 6 bar
COLOR	Light grey RAL 7035

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METROLOGY FOR OPTICS REDEFINED